FIG. 1

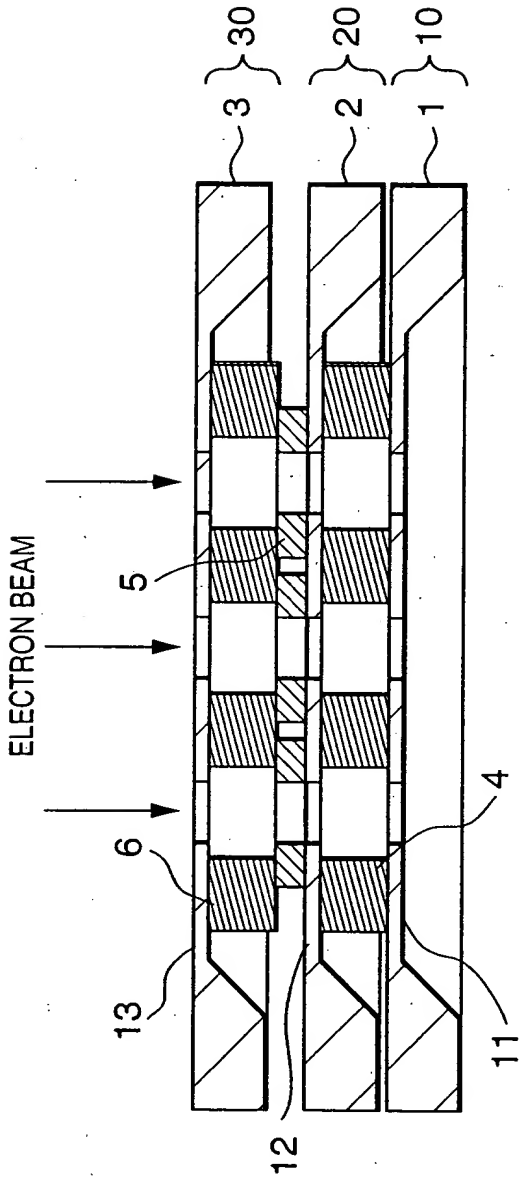

FIG. 2

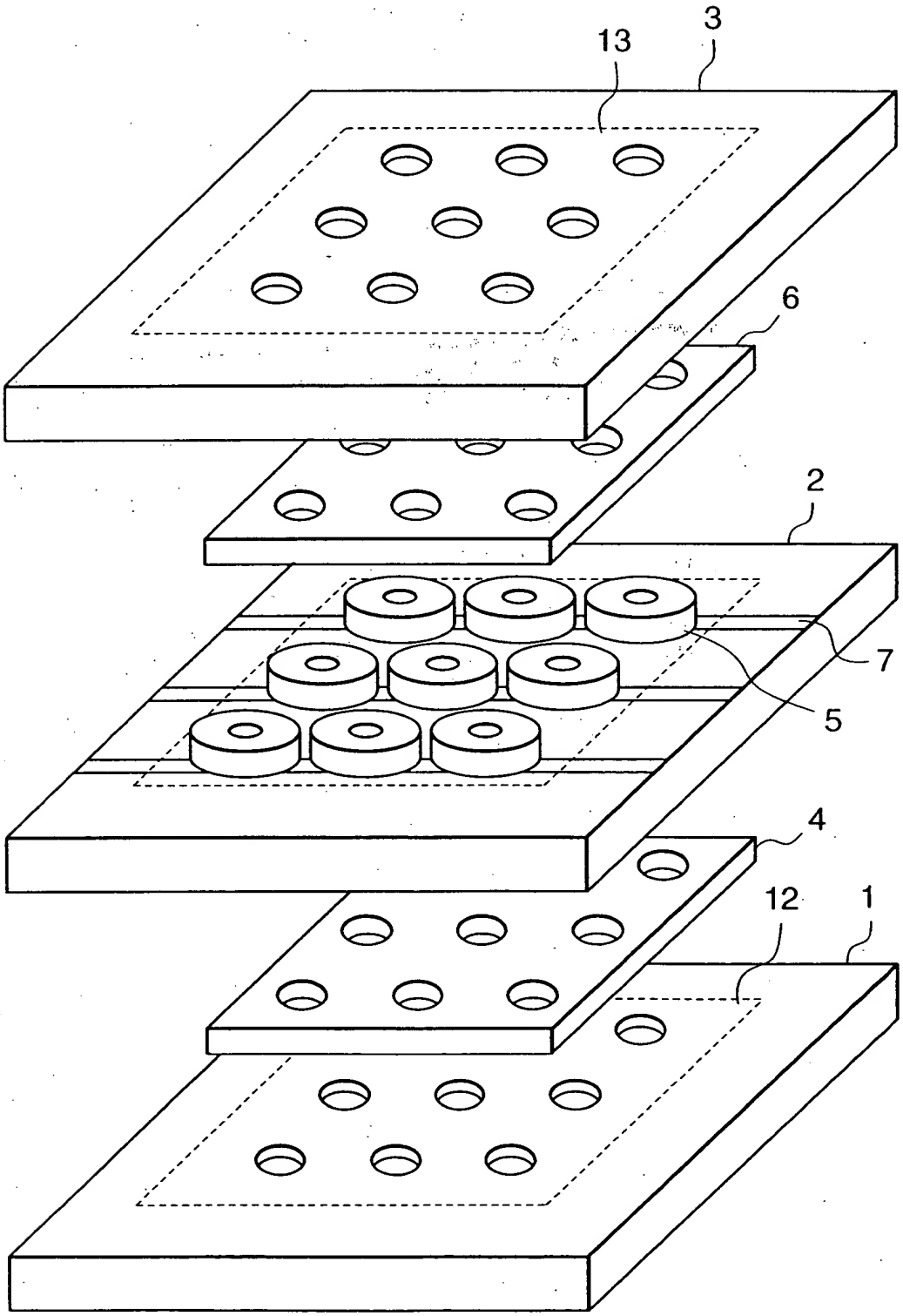

FIG. 3

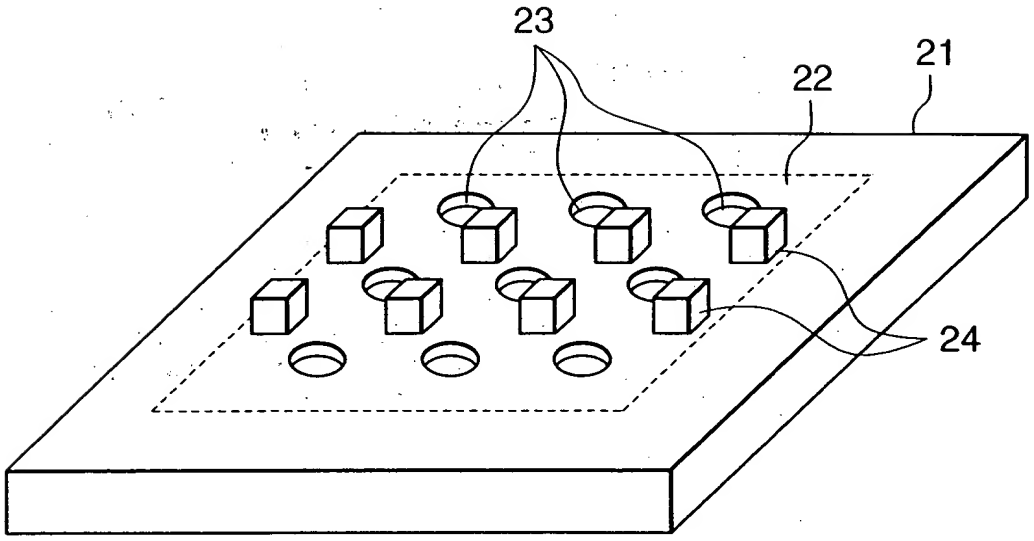

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FIG. 4

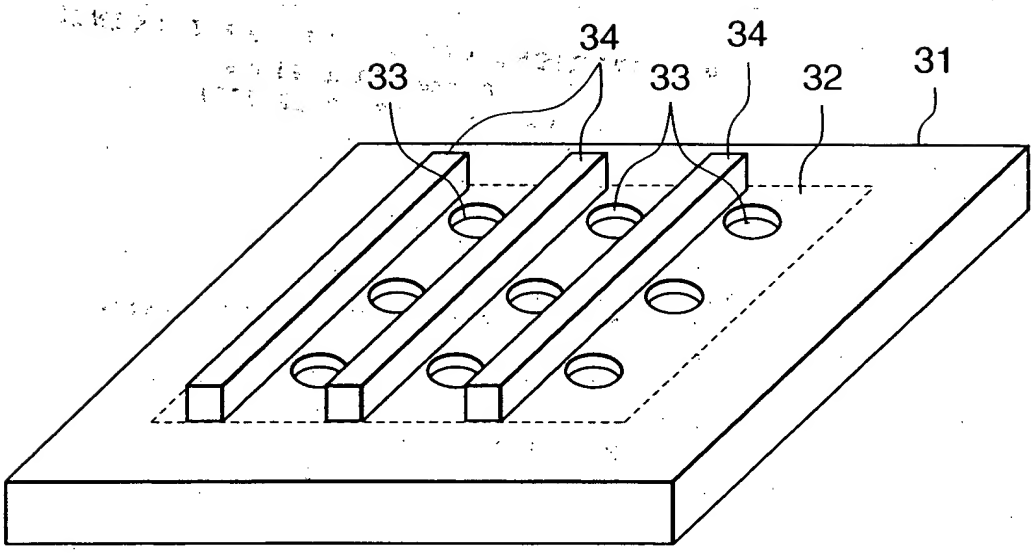


FIG. 5

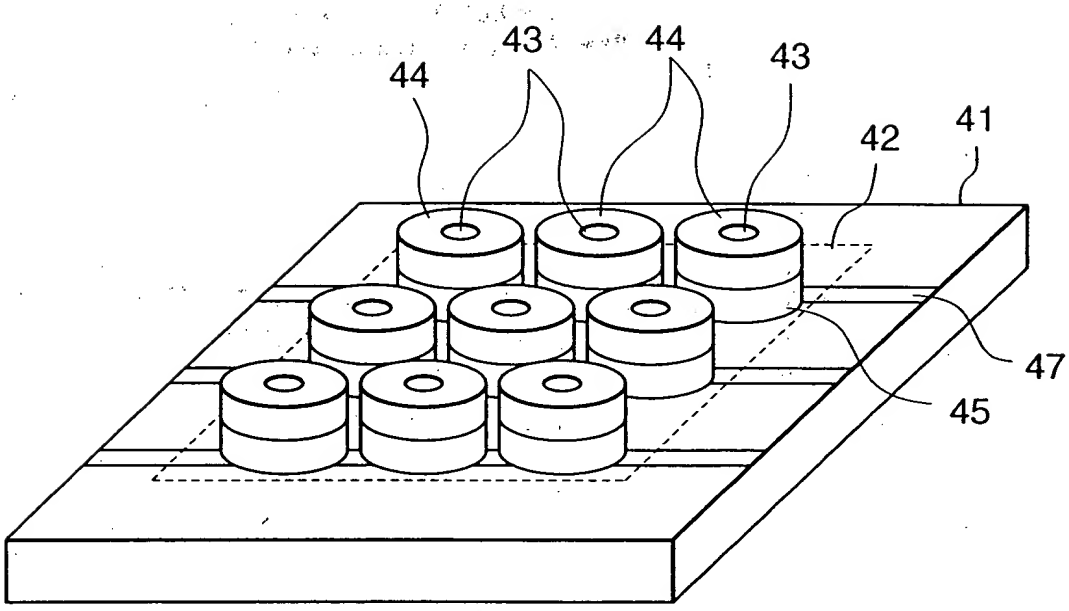


FIG. 6

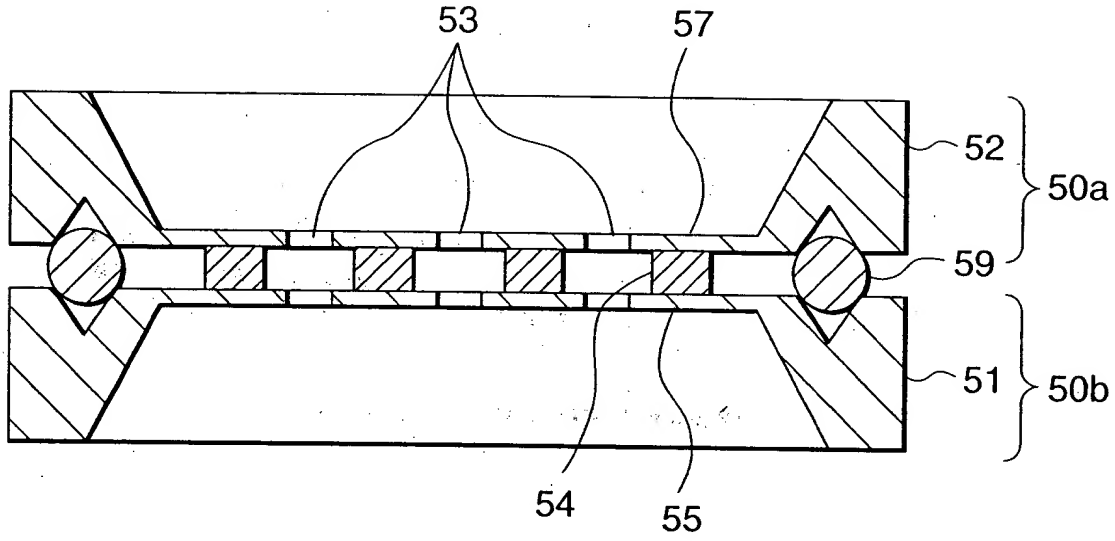


FIG. 7

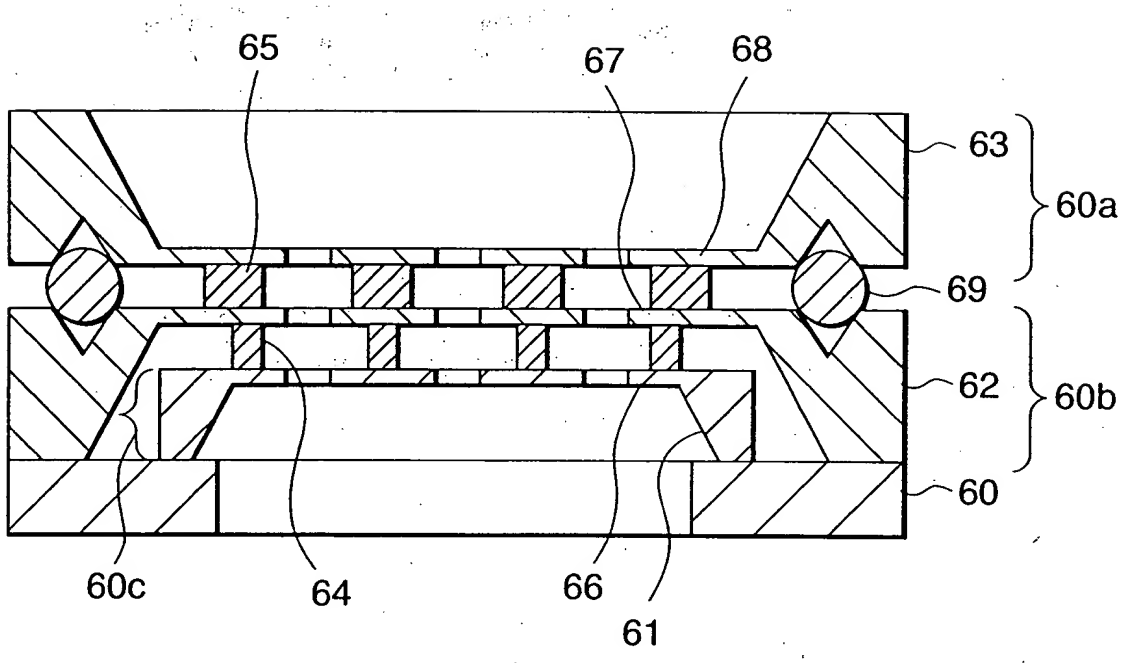


FIG. 8A

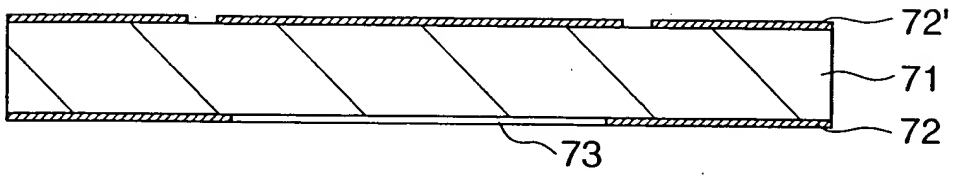


FIG. 8B

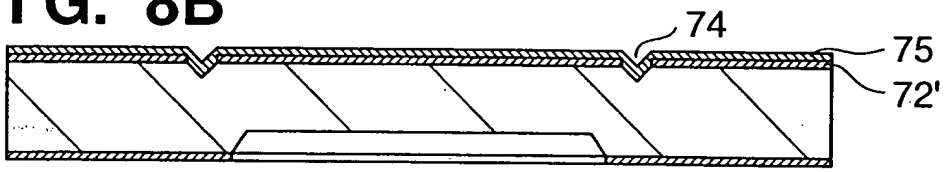


FIG. 8C

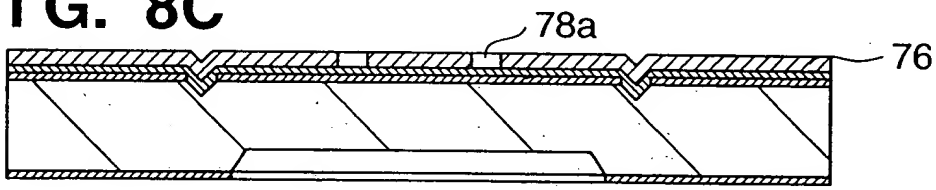


FIG. 8D

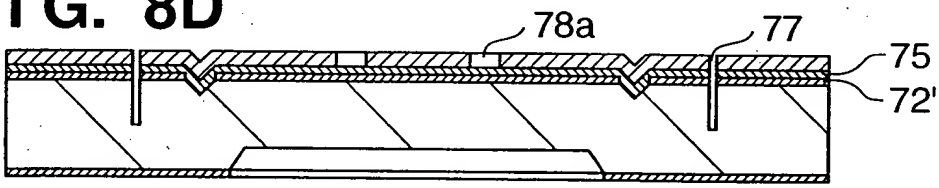


FIG. 8E

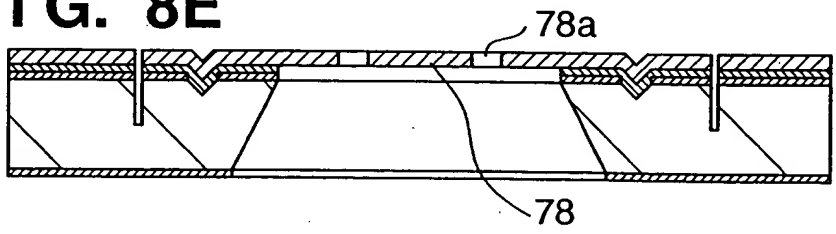


FIG. 8F

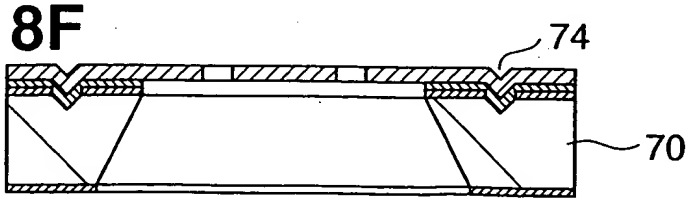


FIG. 9A

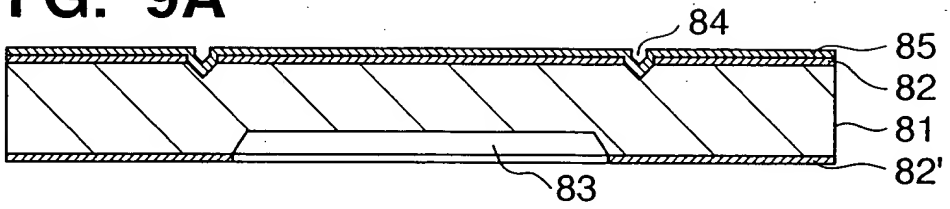


FIG. 9B

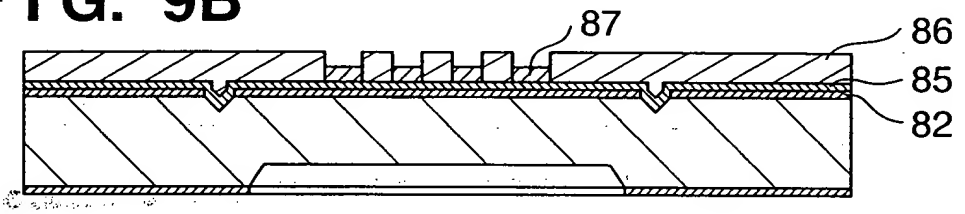


FIG. 9C

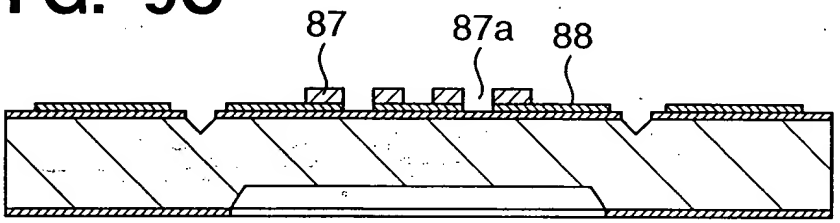


FIG. 9D

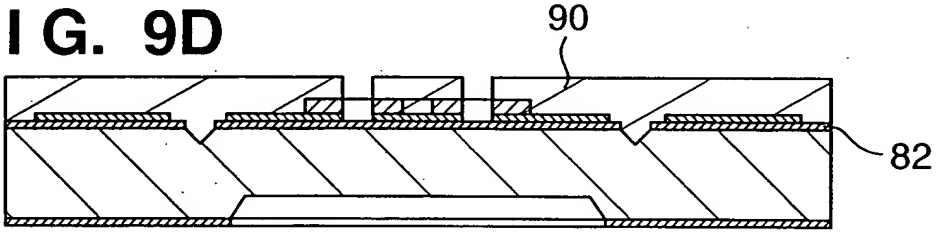


FIG. 9E

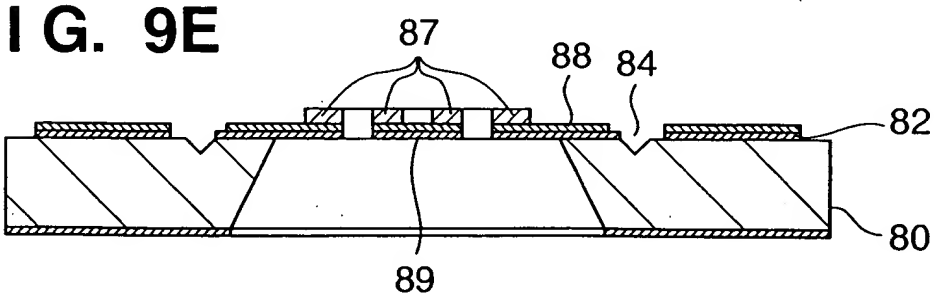


FIG. 10

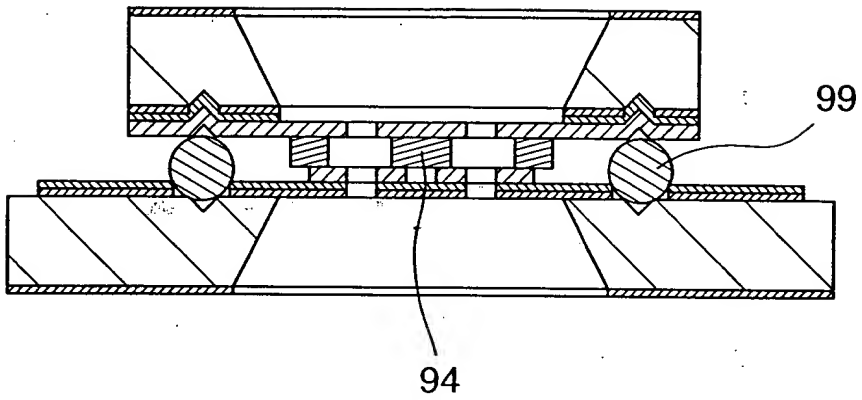
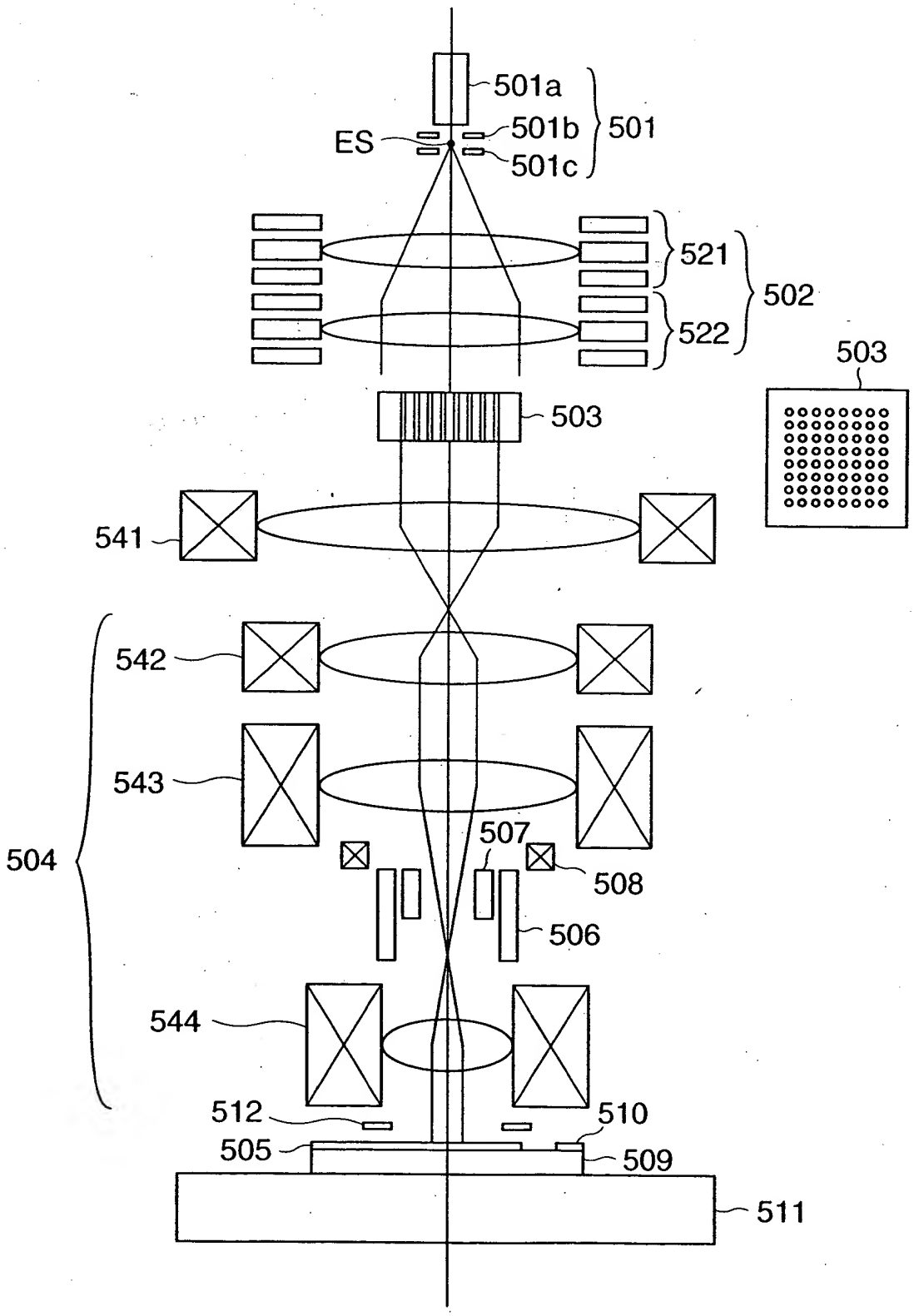


FIG. 11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501b
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ES
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FIG. 12A

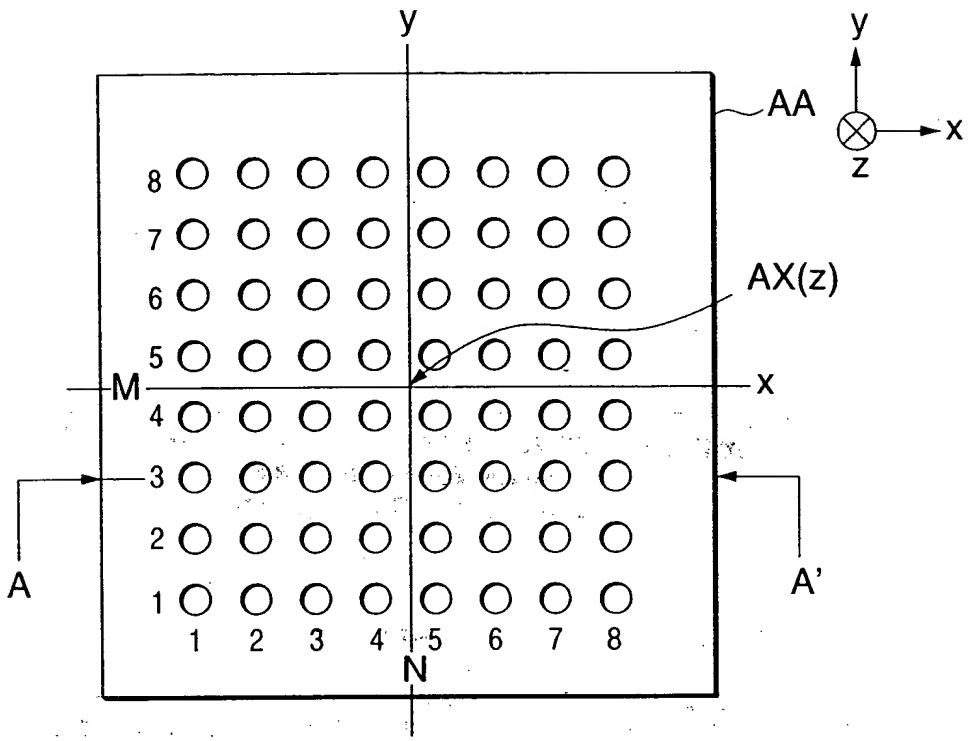

FIG. 12B

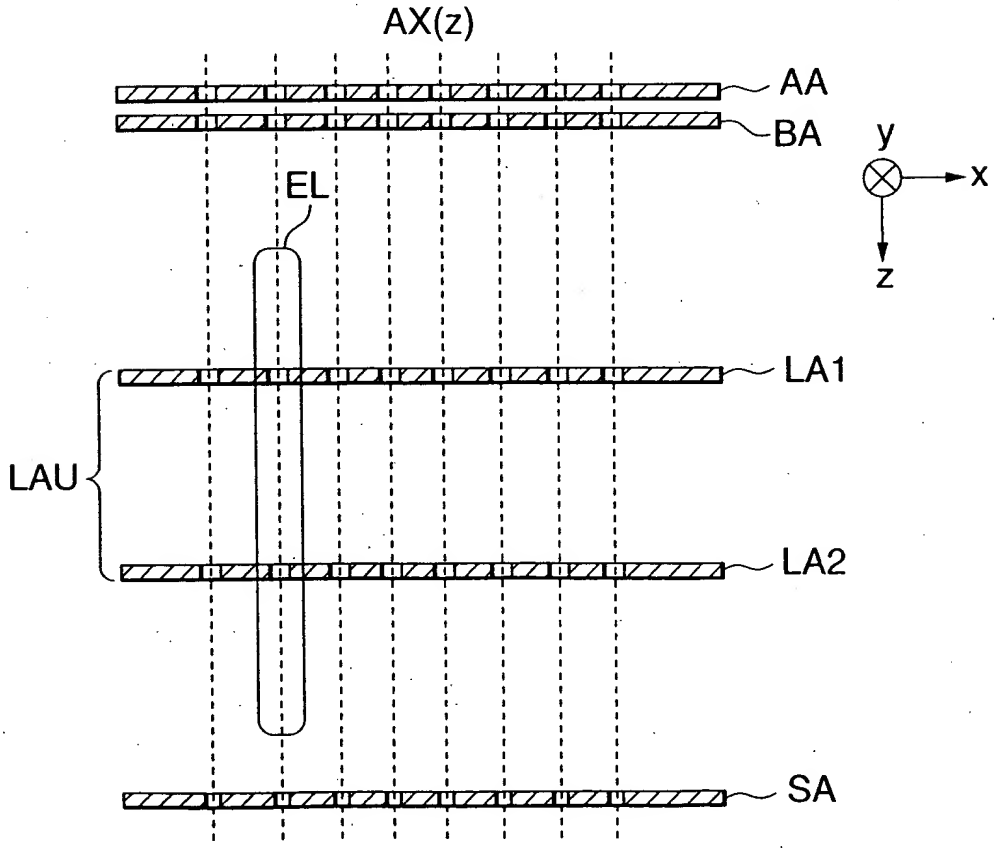

FIG. 13

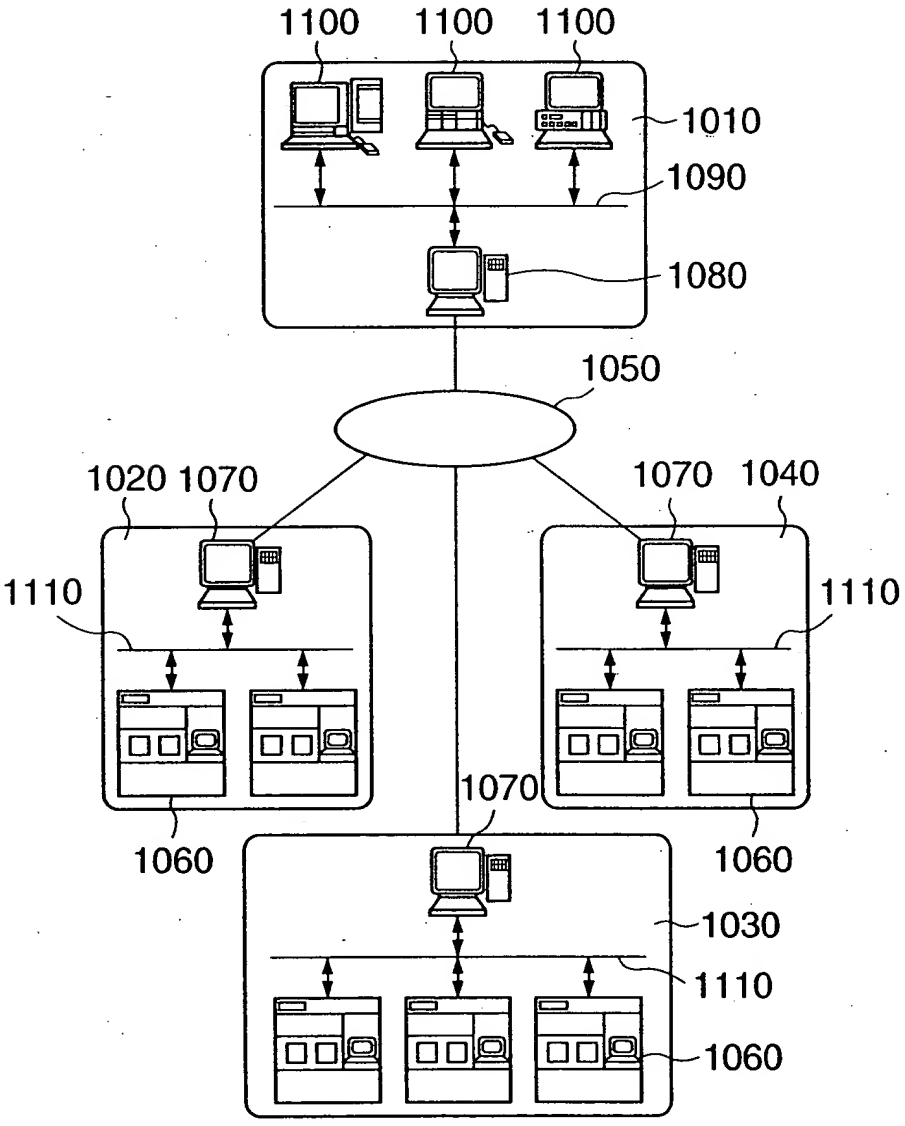
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FIG. 14

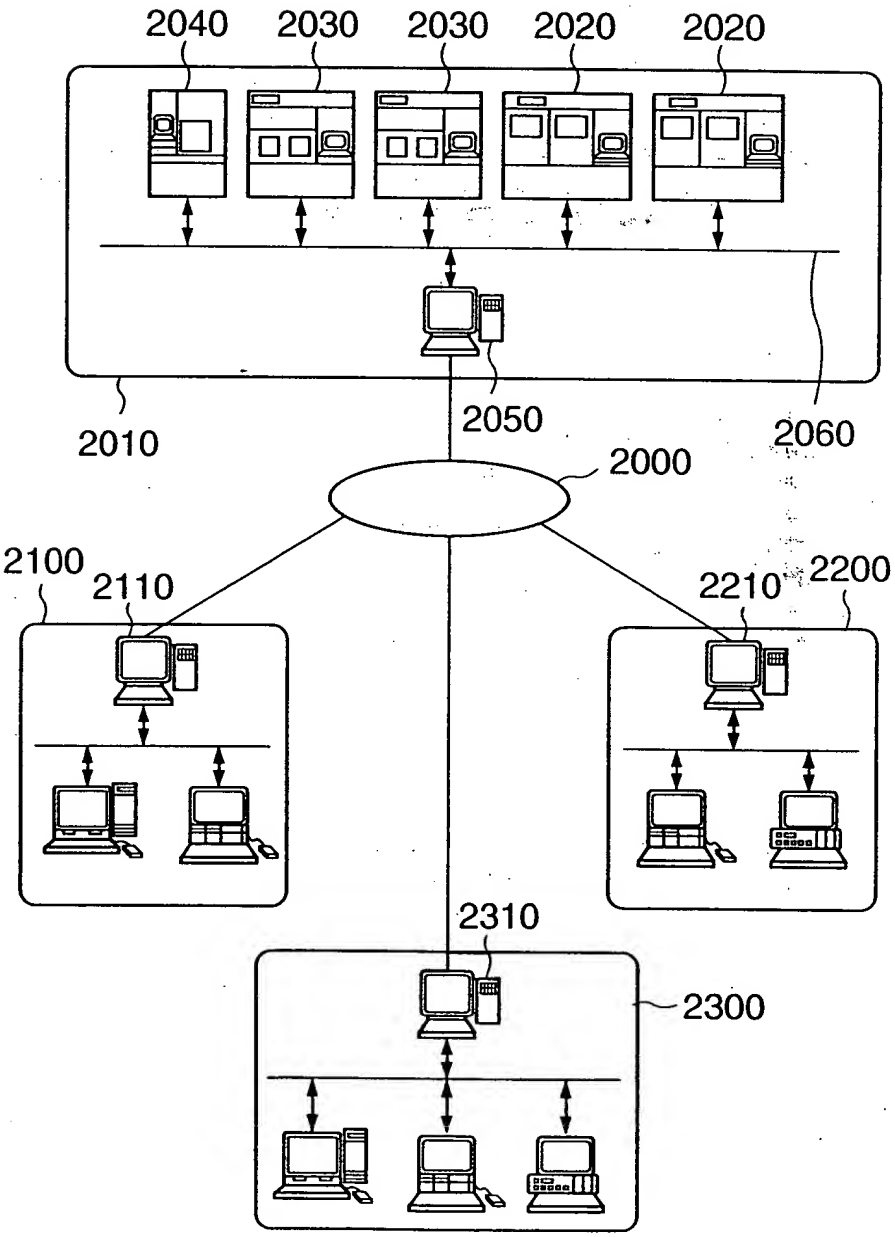
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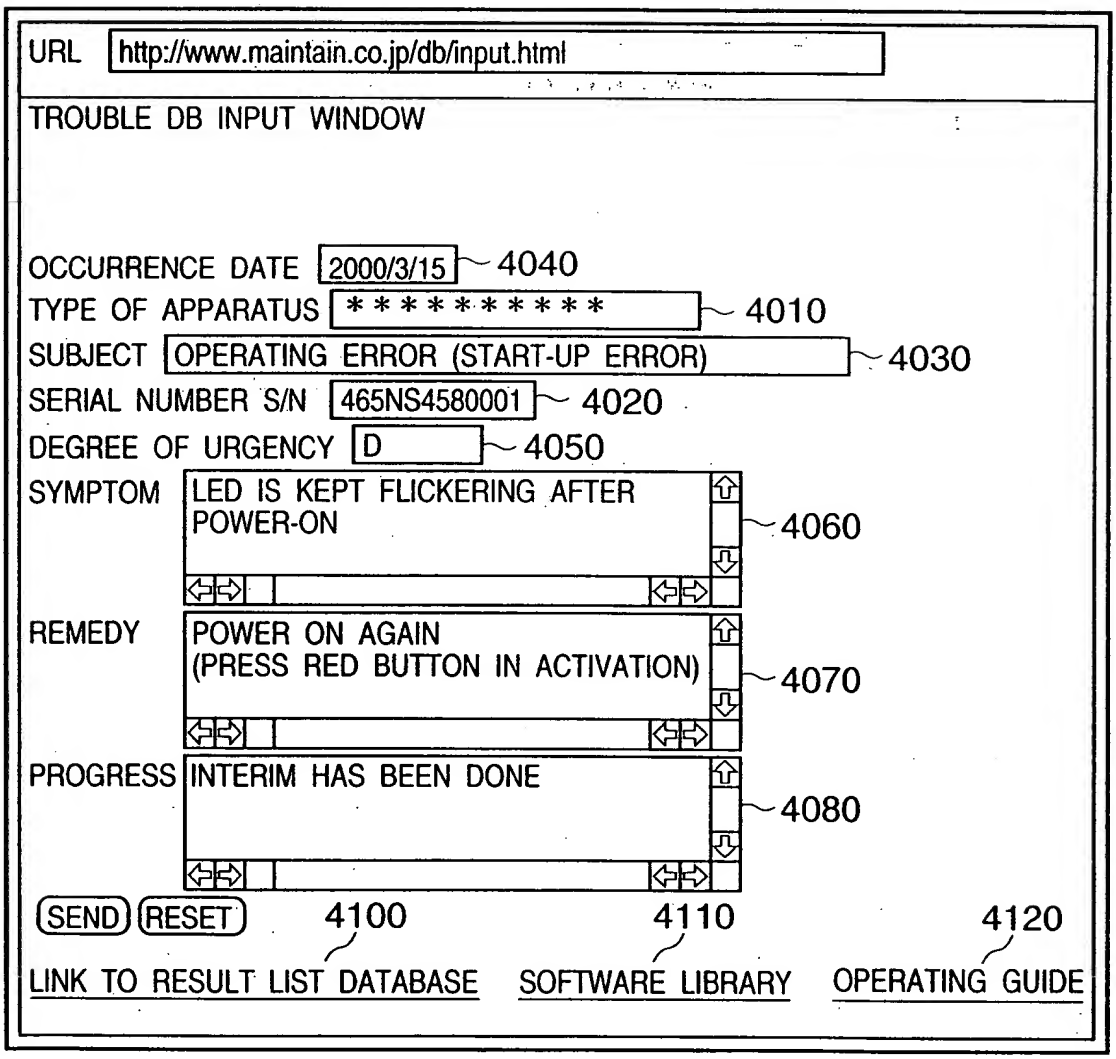
FIG. 15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TROUBLE DB INPUT WINDOW
OCCURRENCE DATE
2000/3/15
4040
TYPE OF APPARATUS
****
4010
SUBJECT
OPERATING ERROR (START-UP ERROR)
4030
SERIAL NUMBER S/N
465NS4580001
4020
DEGREE OF URGENCY
D
4050
SYMPTOM
LED IS KEPT FLICKERING AFTER POWER-ON
4060
REMEDY
POWER ON AGAIN
(PRESS RED BUTTON IN ACTIVATION)
4070
PROGRESS
INTERIM HAS BEEN DONE
4080
SEND
RESET
4100
4110
4120
LINK TO RESULT LIST DATABASE
SOFTWARE LIBRARY
OPERATING GUIDE

FIG. 16

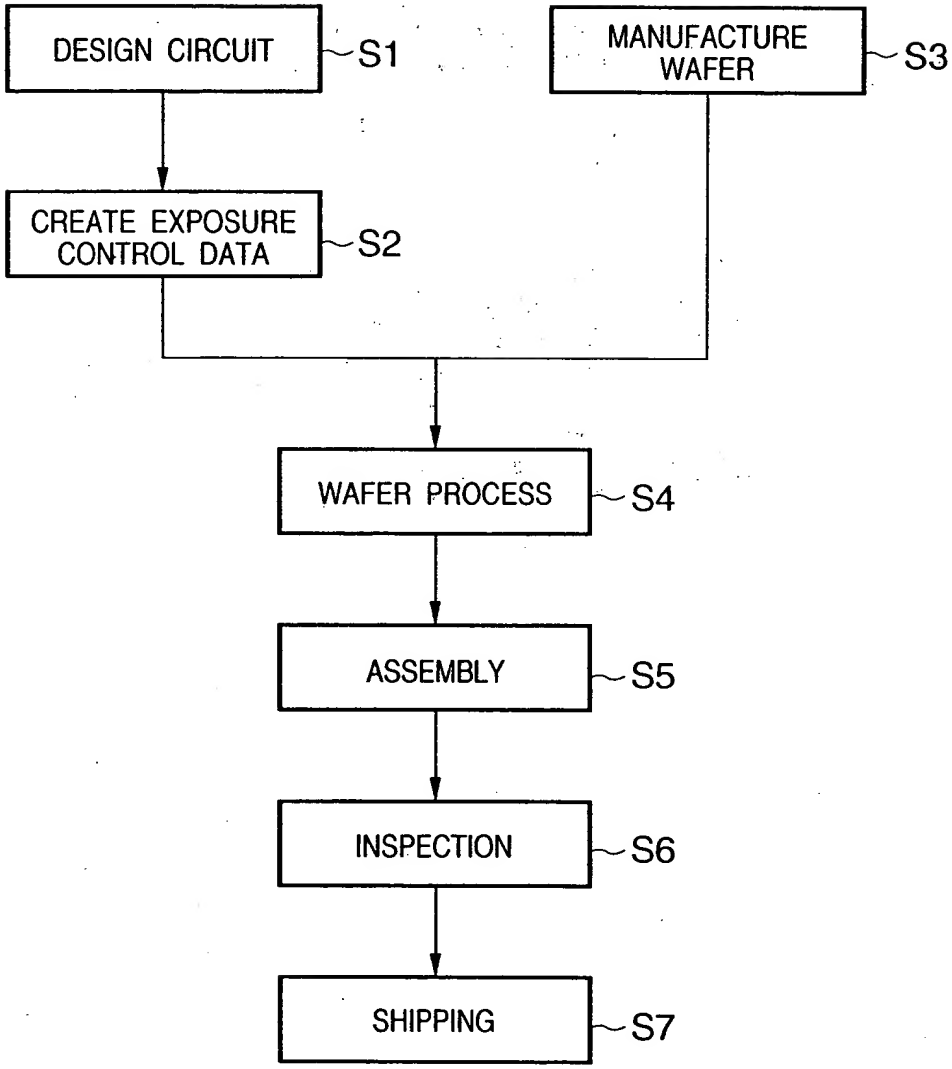
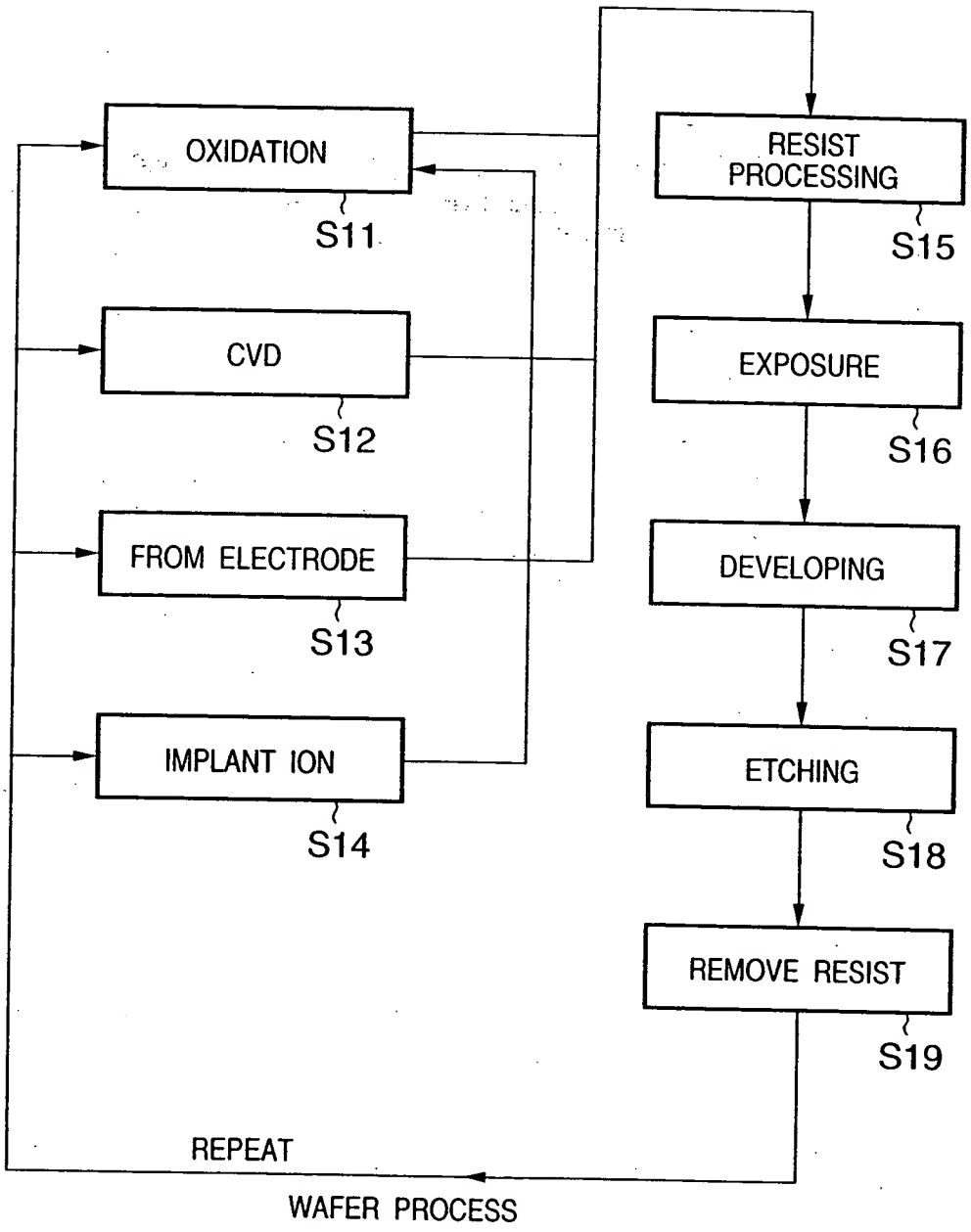

DESIGN CIRCUIT
S1
MANUFACTURE WAFER
S3
CREATE EXPOSURE CONTROL DATA
S2
WAFER PROCESS
S4
ASSEMBLY
S5
INSPECTION
S6
SHIPPING
S7

FIG. 17


OXIDATION
S11
CVD
S12
FROM ELECTRODE
S13
IMPLANT ION
S14
RESIST PROCESSING
S15
EXPOSURE
S16
DEVELOPING
S17
ETCHING
S18
REMOVE RESIST
S19
REPEAT
WAFER PROCESS